**PATENT** S/N Unknown

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:

Wendell P. Noble Jr.

Examiner:

Unknown

Serial No.:

Unknown

Group Art Unit:

Unknown

Filed:

Herewith

Docket:

303.412US4

Title:

VERTICAL GAIN CELL AND ARRAY FOR A DYNAMIC RANDOM ACCESS

MEMORY AND METHOD FOR FORMING THE SAME

## INFORMATION DISCLOSURE STATEMENT

MS Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

In compliance with the duty imposed by 37 C.F.R. § 1.56, and in accordance with 37 C.F.R. §§ 1.97 et. seq., the enclosed materials are brought to the attention of the Examiner for consideration in connection with the above-identified patent application. Applicant respectfully requests that this Information Disclosure Statement be entered and the documents listed on the attached Form 1449 be considered by the Examiner and made of record. Pursuant to the provisions of MPEP 609, Applicant requests that a copy of the 1449 form, initialed as being considered by the Examiner, be returned to the Applicant with the next official communication.

Pursuant to 37 C.F.R. §1.97(b), it is believed that no fee or statement is required with the Information Disclosure Statement.

Pursuant to 37 C.F.R. §1.98(d), copies of the listed documents are not provided as these references were previously cited by or submitted to the U.S. Patent Office in connection with Applicant's prior U.S. application, Serial No. 09/879602, filed on June 12, 2001, which is relied upon for an earlier filing date under 35 U.S.C. §120.

The Examiner is invited to contact the Applicant's Representative at the below-listed telephone number if there are any questions regarding this communication.

Respectfully submitted,

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on of information unless it contains a valid OMB control number.

Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE **Application Number** Unknown STATEMENT BY APPLICANT (Use as many sheets as necessary) Even Date Herewith **Filing Date** Noble Jr., Wendell **First Named Inventor Group Art Unit** Unknown Unknown **Examiner Name** Attorney Docket No: 303.412US4 Sheet 1 of 8

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Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number, Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE **Application Number** Unknown STATEMENT BY APPLICANT Even Date Herewith (Use as many sheets as necessary) **Filing Date** Noble Jr., Wendell **First Named Inventor Group Art Unit** Unknown Unknown **Examiner Name** Attorney Docket No: 303.412US4

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US-5,691,230 11/25/1997 Forbes, L. 437 62 09/04/1996 US-5,696,011 12/09/1997 Yamazaki, S., et al. 437 40 TFI 03/23/1993  US-5,705,415 01/06/1998 Orlowski, Marius K., et al. 437 43 10/04/1994  US-5,714,793 02/03/1998 Cartagena, E., et al. 257 507 08/21/1996  US-5,874,760 02/23/1999 Burns Jr., S. M., et al. 257 315 01/22/1997  US-5,879,971 03/09/1999 Witek, K. 438 238 09/28/1995  US-5,909,400 06/01/1999 Bertin, C. L., et al. 365 187 08/22/1997  US-5,909,618 06/01/1999 Forbes, L., et al. 438 242 07/08/1997  US-5,914,511 06/22/1999 Noble, W. P., et al. 257 302 10/06/1997  US-5,933,717 08/03/1999 Hause, Frederick N., et al. 257 302 03/04/1997  US-5,943,267 08/24/1999 Sekariapuram, S., et al. 365 185.28 06/12/1998  US-6,016,268 01/18/2000 Worley, Eugene R. 365 149 02/05/1998  US-6,172,391 01/09/2001 Goebel, Bernd 257 305 08/27/1998  US-6,181,121 01/30/2001 Kirkland, , et al. 326 41 08/04/1998  US-6,281,8196 01/30/2001 Nguyen, B. 327 539 12/14/1998  US-6,281,876 05/29/2001 Noble, W. P., et al. 438 259 02/27/1998  US-6,221,788 04/24/2001 Kobayashi, H., et al. 438 259 02/27/1998  US-6,242,775 06/05/2001 Noble, Wendell P., et al. 438 259 02/27/1998  US-6,242,775 06/05/2001 Noble, Wendell P., et al. 438 259 02/27/1998  US-6,255,708 07/03/2001 Sudharsanan, R., et al. 257 428 10/10/1997	US-5,644,540	07/01/1997	Manning,	365	200	02/17/1995
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US-5,7/4,793 02/03/1998 Cartagena, E., et al. 257 507 08/21/1996 US-5,874,760 02/23/1999 Burns Jr., S. M., et al. 257 315 01/22/1997 US-5,879,971 03/09/1999 Witek, K. 438 238 09/28/1995 US-5,909,400 06/01/1999 Bertin, C. L., et al. 365 187 08/22/1997 US-5,909,400 06/01/1999 Forbes, L., et al. 365 187 08/22/1997 US-5,909,618 06/01/1999 Forbes, L., et al. 438 242 07/08/1997 US-5,914,511 06/22/1999 Noble, W. P., et al. 257 302 10/06/1997 US-5,933,717 08/03/1999 Hause, Frederick N., et al. 257 302 03/04/1997 US-5,943,267 08/24/1999 Sekariapuram, S., et al. 365 185.28 06/12/1998 US-6,016,268 01/18/2000 Worley, Eugene R. 365 149 02/05/1998 US-6,172,391 01/09/2001 Goebel, Bernd 257 305 08/27/1998 US-6,172,535 01/09/2001 Hopkins, M. 327 66 11/04/1999 US-6,181,121 01/30/2001 Kirkland, , et al. US-6,281,196 01/30/2001 Nguyen, B. 327 539 12/14/1998 US-6,208,164 03/27/2001 Noble, W. P., et al. 326 41 08/04/1998 US-6,238,976 05/29/2001 Noble, W. P., et al. 438 259 02/27/1998 US-6,242,775 06/05/2001 Noble, Wendell P., et al. 438 259 02/27/1998 US-6,255,708 07/03/2001 Sudharsanan, R., et al. 257 428 10/10/1997	US-5,696,011	12/09/1997	Yamazaki, S., et al.	437	40 TFI	03/23/1993
US-5,874,760         02/23/1999         Burns Jr., S. M., et al.         257         315         01/22/1997           US-5,879,971         03/09/1999         Witek, K.         438         238         09/28/1995           US-5,909,400         06/01/1999         Bertin, C. L., et al.         365         187         08/22/1997           US-5,909,618         06/01/1999         Forbes, L., et al.         438         242         07/08/1997           US-5,914,511         06/22/1999         Noble, W. P., et al.         257         302         10/06/1997           US-5,933,717         08/03/1999         Hause, Frederick N., et al.         438         200         03/04/1997           US-5,943,267         08/24/1999         Sekariapuram, S., et al.         365         185.28         06/12/1998           US-5,998,820         12/07/1999         Chi, M., et al.         257         296         11/24/1998           US-6,016,268         01/18/2000         Worley, Eugene R.         365         149         02/05/1998           US-6,172,391         01/09/2001         Goebel, Bernd         257         305         08/27/1998           US-6,181,121         01/30/2001         Kirkland, , et al.         327         539         12/14/1998 <td< td=""><td>US-5,705,415</td><td>01/06/1998</td><td></td><td>437</td><td>43</td><td>10/04/1994</td></td<>	US-5,705,415	01/06/1998		437	43	10/04/1994
US-5,879,971         03/09/1999         Witek, K.         438         238         09/28/1995           US-5,909,400         06/01/1999         Bertin, C. L., et al.         365         187         08/22/1997           US-5,909,618         06/01/1999         Forbes, L., et al.         438         242         07/08/1997           US-5,914,511         06/22/1999         Noble, W. P., et al.         257         302         10/06/1997           US-5,933,717         08/03/1999         Hause, Frederick N., et al.         257         302         10/06/1997           US-5,943,267         08/24/1999         Sekariapuram, S., et al.         365         185.28         06/12/1998           US-5,998,820         12/07/1999         Chi, M, et al.         257         296         11/24/1998           US-6,016,268         01/18/2000         Worley, Eugene R.         365         149         02/05/1998           US-6,172,391         01/09/2001         Goebel, Bernd         257         305         08/27/1998           US-6,181,121         01/30/2001         Kirkland, , et al.         327         539         12/14/1998           US-6,208,164         03/27/2001         Noble, W.P., et al.         326         41         08/04/1998           US-6,2	US-5,714,793	02/03/1998	Cartagena, E., et al.	257	507	08/21/1996
US-5,909,400         06/01/1999         Bertin, C. L., et al.         365         187         08/22/1997           US-5,909,618         06/01/1999         Forbes, L., et al.         438         242         07/08/1997           US-5,914,511         06/22/1999         Noble, W. P., et al.         257         302         10/06/1997           US-5,933,717         08/03/1999         Hause, Frederick N., et al.         438         200         03/04/1997           US-5,943,267         08/24/1999         Sekariapuram, S., et al.         365         185.28         06/12/1998           US-5,998,820         12/07/1999         Chi, M., et al.         257         296         11/24/1998           US-6,016,268         01/18/2000         Worley, Eugene R.         365         149         02/05/1998           US-6,172,391         01/09/2001         Goebel, Bernd         257         305         08/27/1998           US-6,181,121         01/30/2001         Kirkland, , et al.         327         66         11/04/1999           US-6,208,164         03/27/2001         Noble, W. P., et al.         326         41         08/04/1998           US-6,221,788         04/24/2001         Kobayashi, H., et al.         438         762         12/18/1998	US-5,874,760	02/23/1999	Burns Jr., S. M., et al.	257	315	01/22/1997
US-5,909,618 06/01/1999 Forbes, L. , et al. 438 242 07/08/1997 US-5,914,511 06/22/1999 Noble, W. P., et al. 257 302 10/06/1997 US-5,933,717 08/03/1999 Hause, Frederick N., et al. 365 185.28 06/12/1998 US-5,943,267 08/24/1999 Sekariapuram, S. , et al. 365 185.28 06/12/1998 US-5,998,820 12/07/1999 Chi, M , et al. 257 296 11/24/1998 US-6,016,268 01/18/2000 Worley, Eugene R. 365 149 02/05/1998 US-6,172,391 01/09/2001 Goebel, Bernd 257 305 08/27/1998 US-6,172,535 01/09/2001 Hopkins, M. 327 66 11/04/1999 US-6,181,121 01/30/2001 Kirkland, , et al. US-6,181,196 01/30/2001 Nguyen, B. 327 539 12/14/1998 US-6,208,164 03/27/2001 Noble, W. P., et al. 326 41 08/04/1998 US-6,221,788 04/24/2001 Kobayashi, H. , et al. 438 762 12/18/1998 US-6,238,976 05/29/2001 Noble, Wendell P., et al. 438 259 02/27/1998 US-6,255,708 07/03/2001 Sudharsanan, R. , et al. 257 428 10/10/1997	US-5,879,971	03/09/1999	Witek, K.	438	238	09/28/1995
US-5,914,511         06/22/1999         Noble, W. P., et al.         257         302         10/06/1997           US-5,933,717         08/03/1999         Hause, Frederick N., et al.         438         200         03/04/1997           US-5,943,267         08/24/1999         Sekariapuram, S., et al.         365         185.28         06/12/1998           US-5,998,820         12/07/1999         Chi, M., et al.         257         296         11/24/1998           US-6,016,268         01/18/2000         Worley, Eugene R.         365         149         02/05/1998           US-6,172,391         01/09/2001         Goebel, Bernd         257         305         08/27/1998           US-6,172,535         01/09/2001         Hopkins, M.         327         66         11/04/1999           US-6,181,121         01/30/2001         Kirkland, , et al.         327         539         12/14/1998           US-6,281,196         01/30/2001         Noble, W. P., et al.         326         41         08/04/1998           US-6,281,788         04/24/2001         Kobayashi, H., et al.         438         762         12/18/1998           US-6,238,976         05/29/2001         Noble, Wendell P., et al.         438         259         02/27/1998	US-5,909,400	06/01/1999	Bertin, C. L., et al.	365	187	08/22/1997
US-5,933,717         08/03/1999         Hause, Frederick N., et al.         438         200         03/04/1997           US-5,943,267         08/24/1999         Sekariapuram, S., et al.         365         185.28         06/12/1998           US-5,998,820         12/07/1999         Chi, M, et al.         257         296         11/24/1998           US-6,016,268         01/18/2000         Worley, Eugene R.         365         149         02/05/1998           US-6,172,391         01/09/2001         Goebel, Bernd         257         305         08/27/1998           US-6,172,535         01/09/2001         Hopkins, M.         327         66         11/04/1999           US-6,181,121         01/30/2001         Kirkland, , et al.         108/04/1998         12/14/1998           US-6,208,164         03/27/2001         Noble, W. P., et al.         326         41         08/04/1998           US-6,221,788         04/24/2001         Kobayashi, H., et al.         438         762         12/18/1998           US-6,238,976         05/29/2001         Noble, Wendell P., et al.         438         259         02/27/1998           US-6,242,775         06/05/2001         Noble, Wendell P.         257         330         02/24/1998           US-6,255,708<	US-5,909,618	06/01/1999	Forbes, L., et al.	438	242	07/08/1997
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Under the Paperwork Reduction Act of 1995, no persons are required to respond to a collection of information unless it contains a valid OMB control number. Substitute for form 1449A/PTO Complete if Known INFORMATION DISCLOSURE **Application Number** Unknown STATEMENT BY APPLICANT Even Date Herewith Filing Date (Use as many sheets as necessary) Noble Jr., Wendell **First Named Inventor Group Art Unit** Unknown Unknown **Examiner Name** Attorney Docket No: 303.412US4 Sheet 3 of 8

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)	Application Number	Unknown		
	Filing Date	Even Date Herewith		
	First Named Inventor	Noble Jr., Wendell		
	Group Art Unit	Unknown		
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Substitute for form 1449A/PTO	Complete if Known			
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use as many sheets as necessary)	Application Number	Unknown		
	Filing Date	Even Date Herewith		
	First Named Inventor	Noble Jr., Wendell		
	Group Art Unit	Unknown		
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